

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	23436	((trench near3 (isolator isolation isolating)) "STI" 'fox' 'locos') with (opening trench hole recess via groove damascene)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/03 08:38
L2	573	1 and (mask\$3 hard adj mask\$3 hardmask\$3) near5 ("W" tungsten titanium near3 nitride "TiN" amorphous near2 carbon)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/03 08:40
L3	454	2 and (polishing planar planari\$5 'cmp' chemical adj mechanical)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/03 08:39
L4	456	2 and (polish\$3 planar planari\$5 'cmp' chemical adj mechanical)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/03 08:39
L5	414	4 and (mask\$3 hard adj mask\$3 hardmask\$3) near5 (etch\$3 over adj ech\$3)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/03 08:41
L6	400	4 and (mask\$3 hard adj mask\$3 hardmask\$3) near4 (etch\$3 over adj ech\$3)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/03 08:41
L7	359	4 and (mask\$3 hard adj mask\$3 hardmask\$3) near3 (etch\$3 over adj ech\$3)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/03 08:41
L8	337	4 and (mask\$3 hard adj mask\$3 hardmask\$3) near2 (etch\$3 over adj ech\$3)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/03 08:41
L9	269	4 and (mask\$3 hard adj mask\$3 hardmask\$3) near (etch\$3 over adj ech\$3)	US-PGPU B; USPAT; EPO; JPO	OR	ON	2005/08/03 08:41